

HELIOS series

Technical data

System		HELIOS 400	HELIOS 800
Technology		Plasma-assisted reactive magnetron-sputtering (PARMS)	
Applications		DC sputtering (optional: HF sputtering)	
Coating material		SiO ₂ , Nb ₂ O ₅ , Ta ₂ O ₅ , ZrO ₅ , HfO ₂ , AlO ₃ , Si ₃ N ₄	
Capacity		12* pcs. at Ø 125 mm / 5"	12* pcs. at Ø 200 mm / 8"
		16* pcs. at Ø 100 mm / 4"	
Source positions (max. 4)	1 and 2 (standard)	Dual-magnetron	Dual-magnetron
	3 (optional)	Single-magnetron	Dual-magnetron
	4 (standard)	RF plasma	RF plasma
	Coating Ø (standard)	≤100 mm / ≤ 4"	≤ 200 mm / ≤ 8"
	(optional)		≤ 150 mm / ≤ 6"
Layer monitoring	Time control	Yes	Yes
	Optical monitoring	LEYBOLD OPTICS OMS 5100 LEYBOLD OPTICS BBM	LEYBOLD OPTICS OMS 5100 LEYBOLD OPTICS BBM
Dimensions	Width x length x height	5.7 m x 3.4 m x 2.6 m 223" x 134" x 102"	7.3 m x 6.2 m x 3.0 m 288" x 242" x 118"
Site requirements	Electric power	46 kVA	110 kVA
	Line voltage	400 VAC, 50/60 Hz	400 VAC, 50/60 Hz
	System weight	3420 kg	4200 kg